

Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



High throughput Electron beam evaporator

EVA760



by

allianceconcept

High productivity and low up time, the machine EVA760 is a partner for your success

Thanks to its volume, the EVA760 system can be set up using a **wide range of complex configurations**.

This configurable equipment as well as all the others products of the range, can handle a large number of substrates per run.

Its generously sized pumping system ensures a high throughput.

Combined optical and mechanical (quartz) thickness measurement, ion assisted deposition (IAD), co-evaporation, partial pressures regulation through RGA, glow discharge... are all features that can be integrated into your system.



Main features

Vacuum chamber diameter :	760 mm
Height :	920 mm
Volume :	520 litres
Ultimate vacuum (cryogenic configuration) :	5.10^{-8} mbar ^[1]
System throughput :	10 x 6"
Planar configuration uniformity :	< +/- 5% ^[1]
Through the wall installation :	Yes
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

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